

# Advanced Optical Metrology Solutions to Enable APC for CMP

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# AGENDA

Nova IM portfolio for OCD

Process Control Trend

APC enabling OCD applications using NOVA

- FEOL : POST CMP correction
- RMG : W2W improvement with FB control
- BEOL : FF and FB process control

Summary

# Nova IM Portfolio



Nova has 100% market share in pure play Foundries

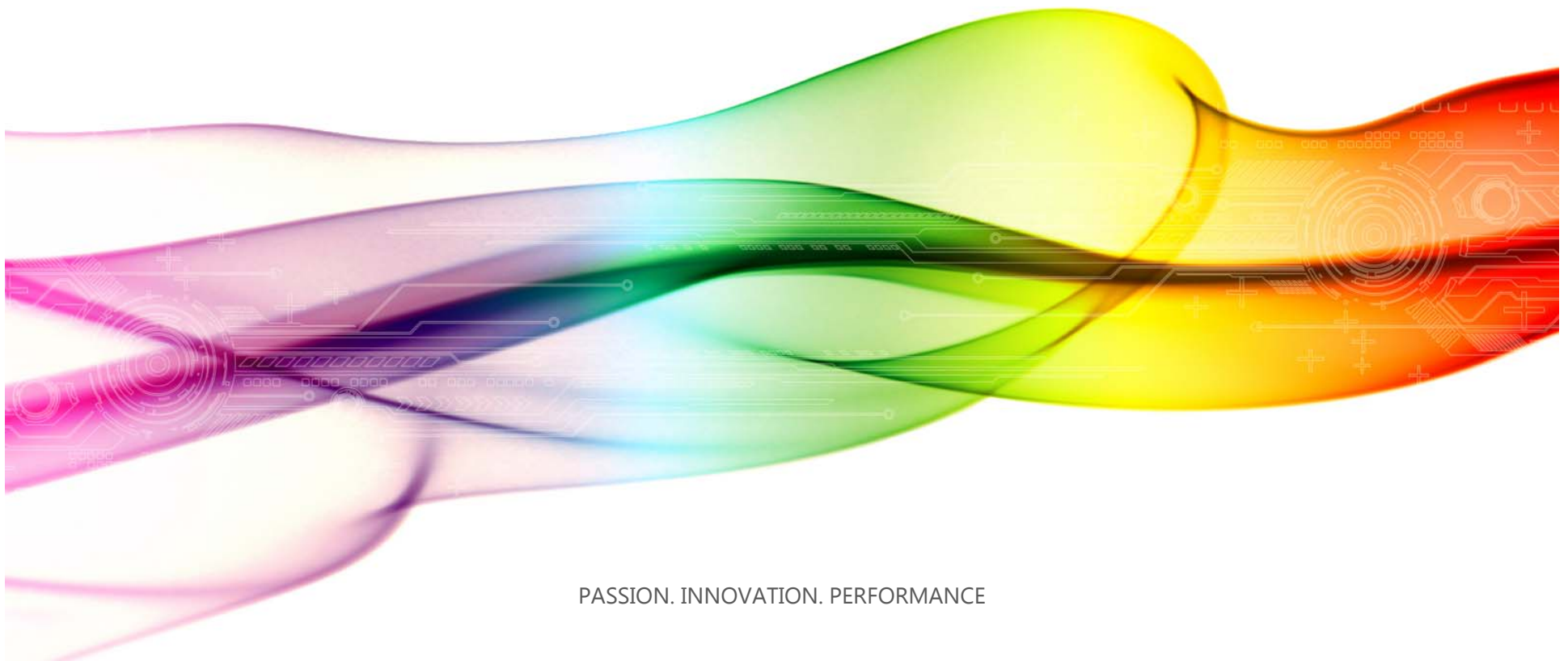
# Summary

- Reviewed CMP applications use process control with OCD on integrated metrology system
- Proved gate uniformity improvement with post CMP correction - L2L variation, WiW variation
- Gate Height variation in device structure improved at RMG using integrated metrology system
- Electrical resistance variability improved by using APC control of polish time using feed forward feed-back APC architecture

# Contact Information

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# THANK YOU



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